
October 20 (Tue.), 2026

[Oral 05] AI & ML for CMP / Process Control

16:55-17:55

International Conference Hall (B1F)

● Session Chair: Chao-Cheng Arthur Chen (NTUST, Taiwan)

16:55-17:15 [AI-Enabled CMP Process Optimization in Advanced Semiconductor](#)
[Oral 05-1] [Manufacturing](#)

Cheng Zhongyao (Inst. for Infocomm Research (I2R), Singapore), Su Myat Noe, Leong Lup San, Chen Gim Guan (Inst. for Microelectronics (IME), Singapore), Qian Peisheng, Ata Kircali Sezin, Gopinathan Arjunan, [Ashish James](#) (Inst. for Infocomm Research (I2R),

17:15-17:35 [Digital-Twin-Based Evaluation of Virtual Metrology Outputs for APC Decision](#)
[Oral 05-2] [Quality in CMP](#)

[Seungchoun Choi](#), Yonghwan Yim, and Semyeong Oh (Amously Inc., Korea)

17:35-17:55 [Accelerating CMP Model Development Using Machine Learning for Early](#)
[Oral 05-3] [Manufacturability Risk Detection](#)

Ushasree Katakamsetty (Globalfoundries Singapore Pte. Ltd., Singapore), Henning Turnow, Boris Vasilev (Globalfoundries Dresden, Germany), and Stefan Nikolaev Voykov (Globalfoundries, Bulgaria), [Ruben Ghulghazaryan](#) (Siemens Industry Software, Armenia), Dav